

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1	(photodiode or photosensor) and (photosensitive near area) and (deposit\$4 near9 dop\$4) near9 (trench or opening or via or recess or aperture or hole) and (buffer near9 (trench or opening or via or recess or aperture or hole))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/13 14:50
L2	14	(photodiode or photosensor) and (photosensitive near area) and (buffer near9 (trench or opening or via or recess or aperture or hole))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/13 14:51
S1	5	((("6566722") or ("6611037")).PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/06/09 13:46
S2	0	S1 and substrate and well and "conductive type" and isolat\$4 and photosensitive and trench\$4 and dop\$4 and anneal and junction	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/09 13:49
S3	0	S1 and substrate and well and p-type and n-type and isolat\$4 and photosensitive and trench\$4 and dop\$4 and anneal and junction	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/09 13:49
S5	0	substrate and well and p-type and n-type and isolat\$4 and photosensitive and trench\$4 and dop\$4 and anneal and junction and cvd and polysilicon and "epitaxial silicon" and buffer and photodiode	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/09 13:50
S6	17	substrate and well and p-type and n-type and isolat\$4 and photosensitive and trench\$4 and dop\$4 and anneal and junction and cvd and polysilicon and "epitaxial silicon" and buffer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/09 13:51
S7	663	substrate and well and (p-type or n-type) and isolat\$4 and photosensitive and trench\$4 and dop\$4 and anneal and junction and cvd and polysilicon or ("epitaxial silicon") and buffer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/09 13:52

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S8	74	substrate and well and (p-type or n-type) and isolat\$4 and photosensitive and trench\$4 and dop\$4 and anneal and junction and cvd and polysilicon or ("epitaxial silicon") and buffer and photodiode	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/09 14:01
S9	53	substrate and well and (p-type or n-type) and isolat\$4 and photosensitive and trench\$4 and dop\$4 and anneal and junction and cvd and polysilicon or ("epitaxial silicon") and buffer and photodiode and (STI or LOCOS)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/09 14:05
S10	9	substrate and "well region" and (p-type or n-type) and isolat\$4 and photosensitive and trench\$4 and dop\$4 and anneal and junction and cvd and polysilicon or ("epitaxial silicon") and buffer and photodiode and (STI or LOCOS)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/09 14:06
S11	93	substrate and well and p-type and n-type and isolat\$4 and photosensitive and trench\$4 and dop\$4 and anneal and junction	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/13 07:49
S12	4	"6569700"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/13 07:53
S13	1171	(trench near9 (well near region))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/13 07:55
S14	597	(trench near9 (well near region)) near9 (substrate or semiconductor or wafer)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/13 07:55
S15	598	(trench\$2 near9 (well near region)) near9 (substrate or semiconductor or wafer)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/13 07:56

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S16	2	(trench\$2 near9 (well near region)) near9 (substrate or semiconductor or wafer) and (photosensitive near4 area)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/13 07:56
S17	11	(trench\$2 near9 (well near region)) near9 (substrate or semiconductor or wafer) and photosensitive	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/13 08:15
S18	4	dop\$4 near9 (trench\$2 near9 (well near region)) near9 (substrate or semiconductor or wafer) and photosensitive	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/13 08:24
S19	8	dop\$4 near9 (trench\$2 near9 (well near region)) near9 (substrate or semiconductor or wafer) and (photosensitive or photodiode)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/13 08:34
S20	65838	(photosensitive or photodiode) near9 (substrate or semiconductor or wafer)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/13 08:39
S21	8359	(photosensitive or photodiode) near9 (substrate or semiconductor or wafer) and well near9 (substrate or wafer or semiconductor)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/13 08:40
S22	238	(photosensitive or photodiode) near9 (substrate or semiconductor or wafer) and (well near9 (substrate or wafer or semiconductor)) and (trench\$2 near9 well)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/13 08:43
S23	145	(photosensitive or photodiode) near9 (substrate or semiconductor or wafer) and (well near9 (substrate or wafer or semiconductor)) and (trench\$2 near9 well) and dop\$4 near9 (substrate or semiconductor or wafer)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/13 08:44

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S24	23	(photosensitive or photodiode) near9 (substrate or semiconductor or wafer) and (well near9 (substrate or wafer or semiconductor)) and (trench\$2 near9 well) and (dop\$4 near9 (substrate or semiconductor or wafer)) and anneal	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/13 08:44
S25	6	(photosensitive or photodiode) near9 (substrate or semiconductor or wafer) and (well near9 (substrate or wafer or semiconductor)) and (trench\$2 near9 well) and (dop\$4 near9 (substrate or semiconductor or wafer)) and anneal and buffer	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/13 12:03
S26	9923	(plural\$4 near9 trench\$2)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/13 12:04
S27	321	(plural\$4 near9 trench\$2) near9 well	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/13 12:04
S28	144	(plural\$4 near9 trench\$2) near9 well near9 (semiconductor or substrate or wafer)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/13 14:21
S29	0	(plural\$4 near9 trench\$2) near9 well near9 (semiconductor or substrate or wafer) and (438/21. ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/02/22 11:44
S30	3	("6611037").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2007/03/21 08:34
S31	0	("(dop\$4nearlayer)near9anneal").PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/03/19 12:14

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S32	193	(dop\$4 near layer) near9 anneal	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/19 12:15
S33	7	(dop\$4 near layer) near9 anneal and (photodiode or photosensor)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/19 12:19
S34	6	(dop\$4 near layer) near9 anneal and (photodiode or photosensor) and (polysilicon or (epitaxial near silicon))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/19 12:19
S35	59	(photosensitive or photosensor) and (buffer near9 (polysilicon or (epitaxial near silicon)))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/21 08:36
S36	5	(photosensitive or photosensor) and (buffer near9 (polysilicon or (epitaxial near silicon))) near9 CVD	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/21 08:38
S37	0	(photosensitive or photosensor) and (buffer near9 (polysilicon or (epitaxial near silicon))) near9 CVD and anneal	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/21 08:38
S38	6	(photosensitive or photosensor) and (buffer near9 (polysilicon or (epitaxial near silicon))) near9 (CVD or "chemical vapor deposition")	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/21 11:55

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S39	9	(photosensitive or photosensor) and (anneal near9 (dop\$4 near layer))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/21 11:56
S40	9	(photosensitive or photosensor or phototransistor) and (anneal near9 (dop\$4 near layer))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/21 12:19
S41	20	(photosensitive or photosensor or phototransistor) and (anneal near9 (buffer near layer))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/21 12:20
S42	0	(photosensitive or photosensor or phototransistor) and (anneal near9 (buffer near layer)) and (dop\$4 near layer)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/21 12:21
S43	17	(photosensitive or photosensor or phototransistor) and (anneal near9 (buffer near layer)) and (dop\$4 near4 layer)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/21 12:21
S44	17	(photosensitive or photosensor or phototransistor) and (anneal near9 (buffer near (layer or film))) and (dop\$4 near4 (layer or film))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/21 12:24
S45	0	(photosensitive or photosensor or phototransistor) and (anneal near9 (buffer near (layer or film))) and (dop\$4 near4 (layer or film)) and ((driv\$4 or disperse or abort) near9 dop\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/21 12:25

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S46	0	(photosensitive or photosensor or phototransistor) and (anneal near9 (buffer near (layer or film))) and (dop\$4 near4 (layer or film)) and ((driv\$4 or dispers\$4 or abort or exit or escap\$4) near9 dop\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/21 12:26
S47	397	photodiode and (substrate or wafer or base) and (well near region) and (isolation near structure) or "STI" and (trench\$2 or via\$4 or hole\$2 or opening\$2 or recess\$2 or aperture\$2) and (dop\$4 near9 well) and photosensitive	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/13 09:36
S48	131	photodiode and (substrate or wafer or base) and (well near region) and (isolation near structure) or "STI" and (trench\$2 or via\$4 or hole\$2 or opening\$2 or recess\$2 or aperture\$2) and (dop\$4 near9 well) and photosensitive and anneal\$4 and (well near region) near9 (substrate or wafer or base)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/13 09:36
S49	122	photodiode and (substrate or wafer or base) and (well near region) and (isolation near structure) or "STI" and (trench\$2 or via\$4 or hole\$2 or opening\$2 or recess\$2 or aperture\$2) and (dop\$4 near9 well) and photosensitive and anneal\$4 and (well near region) near9 (substrate or wafer or base) and (buffer or polysilicon or (epitaxial near silicon)) near9 (well near region) and junction	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/13 10:20
S50	122	photodiode and (substrate or wafer or base) and (well near region) and (isolation near structure) or "STI" and (trench\$2 or via\$4 or hole\$2 or opening\$2 or recess\$2 or aperture\$2) and (dop\$4 near9 well) and (photosensitive near area) and anneal\$4 and (well near region) near9 (substrate or wafer or base) and (buffer or polysilicon or (epitaxial near silicon)) near9 (well near region) and junction and cvd	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/13 10:21

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S51	122	photodiode and (substrate or wafer or base) and (well near region) and (isolation near structure) or "STI" and (trench\$2 or via\$4 or hole\$2 or opening\$2 or recess\$2 or aperture\$2) and (dop\$4 near9 well) and (photosensitive near area) and anneal\$4 and (well near region) near9 (substrate or wafer or base) and (buffer or polysilicon or (epitaxial near silicon)) near9 (well near region) and junction and cvd and fill near9 (trench\$2 or via\$4 or hole\$2 or opening\$2 or recess\$2 or aperture\$2)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/13 10:22
S52	122	photodiode and (substrate or wafer or base) and (well near region) and (isolation near structure) or "STI" and (trench\$2 or via\$4 or hole\$2 or opening\$2 or recess\$2 or aperture\$2) and (dop\$4 near9 well) and (photosensitive near area) and anneal\$4 and (well near region) near9 (substrate or wafer or base) and (buffer or polysilicon or (epitaxial near silicon)) near9 (well near region) and junction and cvd and fill\$4 near4 (trench\$2 or via\$4 or hole\$2 or opening\$2 or recess\$2 or aperture\$2)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/13 11:02
S53	147190	(photodiode or photosensor)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/13 11:03
S54	1516	(photodiode or photosensor) and (photosensitive near area)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/13 11:04
S55	12	(photodiode or photosensor) and (photosensitive near area) and (trench or opening or via or recess or aperture or hole) near9 (well near region)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/13 11:08

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S56	98	(photodiode or photosensor) and (photosensitive near area) and (trench or opening or via or recess or aperture or hole) near9 (photosensitive near area)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/13 11:50
S57	11	(photodiode or photosensor) and (photosensitive near area) and (trench or opening or via or recess or aperture or hole) near9 (photosensitive near area) and (deposit\$4 near9 dop\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/13 11:55
S58	94	(photodiode or photosensor) and (photosensitive near area) and (trench or opening or via or recess or aperture or hole) and (deposit\$4 near9 dop\$4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/13 11:59
S59	15	(photodiode or photosensor) and (photosensitive near area) and (deposit\$4 near9 dop\$4) near9 (trench or opening or via or recess or aperture or hole)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/12/13 14:49